

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of Applicants:

Angelopoulos et al.

Serial No.: 09/256,034

Filed: February 23, 1999

For: MULTILAYERED RESIST SYSTEMS USING TUNED POLYMER
FILMS AS UNDERLAYERS AND METHODS OF FABRICATION THEREOF

Date: April 17, 2001

Group Art Unit: 1752

Examiner: J. Chu

Docket No: YO998-056

Assistant Commissioner for Patents
Washington, DC 20231

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Dr. Daniel P. Morris, Esq.

Reg. No. 32,053

AMENDMENT

In response to Advisory Action dated April 10, 2001, please consider the following:

IN THE SPECIFICATION

Amend the paragraph bridging pages 24 and 25 as follows:

Specially tuned as described in examples 1- 4 Shipley grade 2 novolak resin had been spun coated onto 8" wafers then soft baked at 120C for 30 seconds and hard baked at 252C for 90 seconds using contact hotplates. A thin silicon containing resist described in example 4 is spun on a top of novolac underlayer and baked at 120C for 60 sec. Then resist is exposed to a 248nm radiation at a dose of about 38mJ/cm2 using ASML micstepper and post-exposed baked at 120C for 60 second. Then resist is developed

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